

=> d his

(FILE 'HOME' ENTERED AT 09:42:26 ON 21 JAN 2004)

FILE 'REGISTRY' ENTERED AT 09:43:03 ON 21 JAN 2004

L1 STRUCTURE UPLOADED  
L2 QUE L1  
L3 6 S L1 SSS SAM  
L4 6 S L2 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:44:16 ON 21 JAN 2004

L5 13 S L4  
L6 6 DUPLICATE REMOVE L5 (7 DUPLICATES REMOVED)

FILE 'HOME' ENTERED AT 09:45:09 ON 21 JAN 2004

L7 FILE 'REGISTRY' ENTERED AT 09:48:02 ON 21 JAN 2004  
L8 SCREEN 2067  
L9 STRUCTURE UPLOADED } ①  
L10 QUE L8 AND L7  
L10 0 S L9 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:48:42 ON 21 JAN 2004

L11 0 S L10

FILE 'HOME' ENTERED AT 09:48:58 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:49:27 ON 21 JAN 2004

L12 SCREEN 2067  
L13 STRUCTURE UPLOADED  
L14 QUE L13 AND L12  
L15 0 S L14 SSS SAM

FILE 'HCAPLUS, CAPLUS, USPATFULL' ENTERED AT 09:51:32 ON 21 JAN 2004

L16 0 S L15

FILE 'HOME' ENTERED AT 09:51:43 ON 21 JAN 2004

FILE 'REGISTRY' ENTERED AT 09:54:29 ON 21 JAN 2004

L17 SCREEN 2067  
L18 STRUCTURE UPLOADED } ④  
L19 QUE L18 AND L17  
L20 0 S L19 SSS SAM  
L21 SCREEN 2067  
L22 STRUCTURE UPLOADED } ③  
L23 QUE L22 AND L21  
L24 2 S L23 SSS SAM  
L25 SCREEN 2067  
L26 STRUCTURE UPLOADED }  
L27 QUE L26 AND L25  
L28 0 S L27 SSS SAM  
L29 SCREEN 2067  
L30 STRUCTURE UPLOADED } ②  
L31 QUE L30 AND L29  
L32 1 S L31 SSS SAM

=> FIL HCAPLUS, CAPLUS, USPATFULL  
COST IN U.S. DOLLARS

SINCE FILE  
ENTRY  
3.36

TOTAL  
SESSION  
42.40

FULL ESTIMATED COST

FILE 'HCAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004

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FILE 'CAPLUS' ENTERED AT 09:59:08 ON 21 JAN 2004

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FILE 'USPATFULL' ENTERED AT 09:59:08 ON 21 JAN 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 120

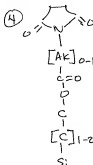
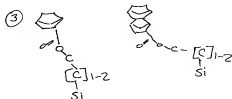
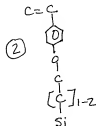
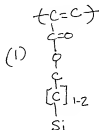
L33 0 L20

=> s 124

L34 11 L24

=> s 128

L35 0 L28



=> a 132  
L36 2 L32  
=> a 134 or 136  
L37 13 L34 OR L36

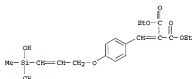
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DUPLICATE PREFERENCE IS 'HCAPLUS, CAPLUS, USPATFULL'  
KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n  
PROCESSING COMPLETED FOR L37  
L38 7 DUPLICATE REMOVE L37 (6 DUPLICATES REMOVED)

=> d 136 1-7 abib hitatr

L38 ANSWER 1 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STM DUPLICATE 1  
ACCESSION NUMBER: 2003:216878 HCAPLUS  
DOCUMENT NUMBER: 138-242881  
TITLE: Skin cosmetic compositions containing active ingredients and specified polysiloxanes  
INVENTOR(S): Hayashi, Kyoko; Mitamura, Joji; Tokunaga, Yoshihiro  
PATENT ASSIGNEE(S): Lion Corp., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 26 pp.  
CODEN: JKKXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2003081806	A2	20030319	JP 2001-270198	20010906
PRIORITY APPL. INFO.:			JP 2001-270198	20010906

IT 501947-86-0D, trimethyl-silyl-terminated  
RL: COS (Cosmetic use); BIOC (Biological study); USES (Uses)  
(assumed monomers; skin cosmetic compns. contg active ingredients and specified polysiloxanes)  
RM 501947-86-0 HCAPLUS  
CM Propenedioic acid, [[4-[[3-(dihydroxymethylsilyl)-2-propenyloxy]phenyl]methylene]-, diethyl ester, homopolymer (9CI) (CA INDEX NAME)  
CM 1  
CRM 200391-14-4  
CMF C18 H24 O7 Si



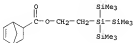
L38 ANSWER 2 OF 7 USPATFULL on STM  
ACCESSION NUMBER: 2003:13168 USPATFULL  
TITLE: Positive working photoresist composition  
INVENTOR(S): Mizutani, Kazuyoshi, Shizuoka, JAPAN  
Sato, Kenichiro, Shizuoka, JAPAN  
Kodama, Kunihiko, Shizuoka, JAPAN  
PATENT ASSIGNEE(S): Fujii Photo Film Co., Ltd., Kanagawa, JAPAN (non-U.S. corporation)

	NUMBER	KIND	DATE
PATENT INFORMATION:	US 6506535	B1	20030114
APPLICATION INFO.:	US 2000-698221		20001030 (9)

	NUMBER	DATE
PRIORITY INFORMATION:	JP 1999-307317	19991028
	JP 1999-311785	19991122
	JP 1999-338487	19991129
	JP 1999-343714	19991202

DOCUMENT TYPE: Utility  
FILE SEGMENT: GRANTED  
PRIMARY EXAMINER: Baxter, Janet  
ASSISTANT EXAMINER: Clarke, Yvette M.

LEGAL REPRESENTATIVE: Sughrue Mion, PLLC  
 NUMBER OF CLAIMS: 19  
 EXEMPLARY CLAIM: 1,3  
 NUMBER OF DRAWINGS: 0 Drawing Figure(s); 0 Drawing Page(s)  
 LINE COUNT: 2346  
 CAS INDEXING IS AVAILABLE FOR THIS PATENT.  
 IT 337954-60-6P  
 [acid-decomposable polymers for high-soln. pos. photoresists giving  
 rectangular patterns]  
 CN 337954-60-6 USPATFULL  
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-(2,2,2-trimethyl-1,1-  
 bis(trimethylsilyl)disilanyl)ethyl ester, polymer with 2,5-furandione  
 and methyl 2-propenoate (SCI) (CA INDEX NAME)  
 CN 1  
 CRN 337954-57-1  
 CNF C19 H40 O2 Si4



CN 2  
 CRN 108-31-6  
 CNF C4 H2 O3



CN 3  
 CRN 96-33-3  
 CNF C4 H6 O2



L38 ANSWER 3 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STM DUPLICATE 2

ACCESSION NUMBER: 2001:726601 HCAPLUS  
 DOCUMENT NUMBER: 135:280511  
 TITLE: Positive-working photoresist compositions showing high resolution and high sensitivity and excellent storage stability  
 INVENTOR(S): Sato, Kenichiro  
 PATENT ASSIGNEE(S): Fujii Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 62 pp.  
 CODEN: JKXKAF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001272784	A2	20011005	JP 2000-385724	20001219
PRIORITY APPLN. INFO.:			JP 1999-363302	A 19991221
			JP 2000-10773	A 20000119
			JP 2000-10774	A 20000119

OTHER SOURCE(S): NARDAT 135:280511  
 IT 363616-65-3P  
 RL: PHU [Preparation, unclassified]; TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 (alk. developing silyl-contg. polymer pos. photoresists having storage stability)  
 CN 363616-65-3 HCAPLUS  
 CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 1,1-dimethyl-3-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]propyl ester, polymer with 2,5-furandione and N-(methylsulfonyl)bicyclo[2.2.1]hept-5-ene-2-

carboxamide (9CI) (CA INDEX NAME)

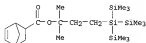
CM 1

CRN 363616-64-2  
CMF C9 H13 N O3 S



CM 2

CRN 250589-01-6  
CMF C22 H46 O2 Si4



CM 3

CRN 108-31-6  
CMF C4 H2 O3



L38 ANSWER 4 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 3

ACCESSION NUMBER: 2001423557 HCAPLUS  
DOCUMENT NUMBER: 13538893  
TITLE: Positive photoresist compositions for manufacture of semiconductor devices  
INVENTOR(S): Sato, Kenichiro; Kodama, Kunihiko; Mizutani, Kazuyoshi  
PATENT ASSIGNEE(S): Fujii Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 66 pp.  
DOCUMENT TYPE: CODEN: JKXKAP  
LANGUAGE: Patent  
FAMILY ACC. NUM. COUNT: Japanese 4  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001159812	A2	20010612	JP 1999-343714	19991202
US 6506535	B1	20030114	US 2000-698221	20001030

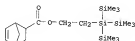
PRIORITY APPLN. INFO.: JP 1999-307317 A 19991028  
JP 1999-331785 A 19991122  
JP 1999-338487 A 19991129  
JP 1999-343714 A 19991202

OTHER SOURCE(S): MARPAT 13538893

IT 337954-60-6P  
EL: IMP (Industrial manufacture); TM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(acid-decomposable polymers; improvement of exposure margin in pos.  
photoresists for manuf. of semiconductor devices)  
RM 337954-60-6 HCAPLUS  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanylethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1  
CMF C19 H40 O2 Si4



CM 2

CRN 108-31-6

CMF C4 H2 O3



CM 3

CRN 96-33-3

CMF C4 H6 O2



LIB ANSWER 5 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 4

ACCESSION NUMBER: 2001:414682 HCAPLUS

DOCUMENT NUMBER: 135:26888

TITLE: Alkali-developable positive-working photoresist composition

INVENTOR(S): Sato, Kenichiro; Mizutani, Kazuyoshi

PATENT ASSIGNER(S): Fujii Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 71 pp.

CODER: JKKKAP

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 4

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001154361	A2	20010608	JP 1999-338487	19991129
US 6504535	B1	20030114	US 2000-698221	20001030
PRIORITY APPLN. INPO:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

IT 337954-60-6P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(polymer in alkali-developable pos.-working photoresist compn.)

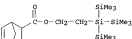
RM 337954-60-6 HCAPLUS

CM bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[(2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilamyl)ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 337954-57-1

CMF C19 H40 O2 Si4



CM 2

CRN 108-31-6

CMF C4 H2 O3



CH 3

CRN 96-33-3  
CMP C4 H6 O2



L38 ANSWER 6 OF 7 HCAPLOS COPYRIGHT 2004 ACS on STM DUPLICATE 5  
ACCESSION NUMBER: 2001.388948 HCAPLUS  
DOCUMENT NUMBER: 135.12122  
TITLE: Positive-working photoresist composition containing  
sulfonium compound acid generator  
INVENTOR(S): Safo, Kenichiro; Mizutani, Kazuyoshi  
PATENT ASSIGNER(S): Fujii Photo Film Co., Ltd., Japan  
SOURCE: Jpn. Kokai Tokkyo Koho, 65 pp.  
CODEN: JKKXAF  
DOCUMENT TYPE: Patent  
LANGUAGE: Japanese  
FAMILY ACC. NUM. COUNT: 4  
PATENT INFORMATION:

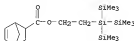
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001147536	A2	20010529	JP 1999-331785	19991122
US 6506535	B1	20030114	US 2000-698221	20001030

PRIORITY APPLN. INFO.: JP 1999-307317 A 19991028  
JP 1999-331785 A 19991122  
JP 1999-338487 A 19991129  
JP 1999-343714 A 19991202

OTHER SOURCE(S): MARPAT 135.12122  
IT 337954-60-6P  
RL: PHU (Preparation, unclassified); TSM (Technical or engineered material use); PREP (Preparation); USGS (Uses)  
(photoresist compn. contg. sulfonium compd. acid generator, acid-decomposable polymer, basic compd. and surfactant)  
RN 337954-60-6 HCAPLUS  
CN Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilanyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9C1) (CA INDEX NAME)

CH 1

CRN 337954-57-1  
CMP C19 H40 O2 Si4



CH 2

CRN 108-31-6  
CMP C4 H2 O3



CH 3

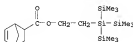
CRN 96-33-3  
CMP C4 H6 O2



L38 ANSWER 7 OF 7 HCAPLUS COPYRIGHT 2004 ACS on STM DUPLICATE 6  
 ACCESSION NUMBER: 2001:336598 HCAPLUS  
 DOCUMENT NUMBER: 134:346473  
 TITLE: High-resolution positive photoresist compositions  
 INVENTOR(S): Mizutani, Kazuyoshi  
 PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan  
 SOURCE: Jpn. Kokai Tokkyo Koho, 60 pp.  
 CODEM: JKKXNF  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Japanese  
 FAMILY ACC. NUM. COUNT: 4  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2001125272	A2	20010511	JP 1999-307317	19991028
US 6506535	B1	20030114	US 2000-698221	20001030
PRIORITY APPL. INFO.:			JP 1999-307317	A 19991028
			JP 1999-331785	A 19991122
			JP 1999-338487	A 19991129
			JP 1999-343714	A 19991202

IT 337954-60-6P  
 RL: IMP (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)  
 [acid-decomposable polymers for high-soln. pos. photoresists giving rectangular patterns]  
 RN 337954-60-6 HCAPLUS  
 CM Bicyclo[2.2.1]hept-5-ene-2-carboxylic acid, 2-[2,2,2-trimethyl-1,1-bis(trimethylsilyl)disilyl]ethyl ester, polymer with 2,5-furandione and methyl 2-propenoate (9C1) (CA INDEX NAME)  
 CM 1  
 CRI 337954-57-1  
 CMI C19 H40 O2 S14



CM 2  
 CRI 108-31-6  
 CMI C4 H2 O3



CM 3  
 CRI 96-33-3  
 CMI C4 H6 O2

